

NOTICE OF LAND USE APPLICATION - SEPA EXEMPT

The public has the right to review the contents of the official file for the proposal, provide written comments, participate in the public hearings/meetings, and request a copy of the final decision. The most current application materials are available for public review by clicking on the application number(s) provided in this notice, or by requesting a link from the staff contact listed in this notice. Comments may be emailed to the staff contact identified in the notice, mailed to the attention of the staff contact to P.O. Box 7380, Bonney Lake, WA 98391, or delivered to the Public Services Department located at 9002 Main Street East, Suite 300, Bonney Lake, WA 98391. Comments will be accepted if filed with the Public Services Department on or before 5PM on 8/30/2021.

Application Submittal:	8/3/2021	Application Complete:	8/10/2021
Notice Date:	8/13/2021	Comment Due Date:	8/30/2021
Application Type:	Design Review		
Project Description:	The applicant proposes to remodel an existing commercial space to convert from a previous use (supermarket) to a clothing retail/department store. The proposal involves interior remodeling and changes to the exterior of the building.		
Project Name:	Kohl's Department Store		
Name of Applicant(s):	Jeff Nance, R.A. Smith Inc.	Site Address:	20025 SR 410 E. Bonney Lake, WA 98391
Application Number(s):	PLN-2021-02608	Tax Parcel Number(s):	0519036029
Environmental Review:	NOTICE IS HEREBY GIVEN that the City has determined that the project described above is categorically exempt from review under the State Environmental Policy Act (SEPA) pursuant to WAC 197-11-800(3).		
Public Hearing:	The above application is classified as Type 2 Permit pursuant to BLMC 14.30.010 and does not require a public hearing pursuant to BLMC 14.30.020.		
Other Applications:	Civil permit(s), building permit(s)		
Staff Contact:	Nate Schildmeyer, Associate Planner; (253) 447-4350 or schildmeyern@cobl.us		
Documentation Available:	Elevation illustrations, site/landscaping plan, photometric plan, application		